

# Resource Summary Report

Generated by [kravitz2](#) on Jul 29, 2026

## JEOL: JBX-8100FS Electron Beam Lithography System

RRID:SCR\_020170

Type: Tool

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### Proper Citation

JEOL: JBX-8100FS Electron Beam Lithography System (RRID:SCR\_020170)

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### Resource Information

**URL:** <https://www.jeolusa.com/PRODUCTS/Photomask-Direct-Write-Lithography/Electron-Beam-Lithography/JBX-8100FS>

**Proper Citation:** JEOL: JBX-8100FS Electron Beam Lithography System (RRID:SCR\_020170)

**Description:** Electron beam lithography system that writes ultrafine patterns at faster rate of speed while minimizing idle time, especially during exposure process, thus increasing throughput.

**Resource Type:** instrument resource

**Keywords:** Jeol, JEOL, Electron Beam Lithography System, Instrument Equipment, USEDit,

**Availability:** Commercially available

**Resource Name:** JEOL: JBX-8100FS Electron Beam Lithography System

**Resource ID:** SCR\_020170

**Alternate IDs:** Model\_Number\_JBX\_8100FS

**Record Creation Time:** 20220129T080349+0000

**Record Last Update:** 20260725T190922+0000

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### Ratings and Alerts

No rating or validation information has been found for JEOL: JBX-8100FS Electron Beam Lithography System.

No alerts have been found for JEOL: JBX-8100FS Electron Beam Lithography System.

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## Data and Source Information

**Source:** [SciCrunch Registry](#)

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## Usage and Citation Metrics

We have not found any literature mentions for this resource.